

pressure, *T* is the thickness of the sheet, and  $\sigma_c$  is the flow<br>stress of the material that is being formed. The slope of the<br>stress of the material that is being formed. The slope of the<br>stress imilar to the strain ra

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## J. STOLK and A. MANTHIRAM

Heat dissipation and thermal expansion mismatch are extremely important issues in many electrical and electronics Fig. 6—Plot of forming pressure, *P*, against average rate of forming, *dH*/*dt*. applications, and the materials used for thermal management in such applications have attracted a great deal of attention in recent years. The move in the microelectronics industry toward higher circuit board chip densities and packageless

cavitation is likely to be delayed if superplastic forming<br>
is done at temperatures beyond 950 °C.<br>
Cone heights as a function of forming pressure after 1<br>
cone heights as a function of forming pressure after 1<br>
mismatch

In conclusion, preliminary attempts were made to super-<br>plastically form duplex stainless steel. Because of the limita-<br>plastically form duplex stainless steel. Because of the limita-<br>tion posed by the SPF machine, maximu molybdenum content. The copper molybdate precipitate that formed during the reaction was greenish, and the silver **REFERENCES** molybdate precipitate was pale yellow. The precipitates were washed repeatedly with water to remove any ions that did

The as-prepared Cu-Mo-O and Ag-Mo-O powders were

<sup>5.</sup> M. Sagaradi, D. Pulino-Sagaradi, and R.E. Medrano: *Acta Metall.*, J. STOLK, Visiting Assistant Professor, formerly at Texas Materials 1998, vol. 46, pp. 3857-62.<br>
1998, pp. Xashyap, and S. Banerjee: *Mater. Sci.* neering Department, Bucknell University, Lewisburg, PA 17837. A. *Forum*, 1997, vols. 243–245, pp. 663-68. MANTHIRAM, Professor, is with the Texas Materials Institute, The Univer-<br>D. Pulino-Sagaradi, A.M.M. Nazar, J.J. Ammann, and R.E. Medrano: sity of Texas at Austin, Austin, TX 78712.



initially heated in H<sub>2</sub> to reduce the compounds to metallic small grain size, and hardness increases with molybdenum Cu and Mo or Ag and Mo. After annealing, the powders content. Were compacted in a hydraulic press and s were compacted in a hydraulic press and sintered at 800 °C In summary, nanocrystalline Cu-Mo-O and Ag-Mo-O to 1050 °C in a H<sub>2</sub> atmosphere X-ray diffraction (XRD) were prepared using simple chemical precursor techniques. to 1050 °C in a H<sub>2</sub> atmosphere. X-ray diffraction (XRD),<br>energy dispersive X-ray spectroscopy (EDS), and scanning<br>electron microscopy (SEM) were used to characterize the<br>products. Thermal expansion behavior was evaluated <sup>8</sup>C to 300 °C with a thermomechanical analyzer. Electrical tivity of the Cu-Mo and Ag-Mo alloys decrease with conductivity was measured by a four-probe technique, and increasing molybdenum content, and specific values of conductivity was measured by a four-probe technique, and increasing molybdenum content, and specific values of CTE<br>thermal conductivity was estimated using the Wiedemann-<br>and conductivity are easily obtainable by this proc thermal conductivity was estimated using the Wiedemann– Franz law. The thermal and electrical properties of the Cu-Mo and

by EDS of several as-prepared Cu-Mo and Ag-Mo powders existing low CTE-high conductivity materials, and the small are shown in Table I. The X-ray diffraction patterns of the grain size and isotropic properties of the fineare shown in Table I. The X-ray diffraction patterns of the as-prepared and heat-treated sample A (52.5 wt pct Cu- offer distinct mechanical property advantages over some of 47.5 wt pct Mo) are shown in Figure 1. In the as-prepared the materials currently in use.

condition, relative intensity is low and no distinct X-ray diffraction reflections are present, indicating extremely small grain size in the as-prepared powder. The broad reflections that are observed in Figure 1(a) for the as-prepared powder correspond to the major peaks of several different Cu*x*Mo*y*O*<sup>z</sup>* copper molybdate compounds such as  $CuMo<sub>4</sub>, Cu<sub>3</sub>Mo<sub>2</sub>O<sub>9</sub>$ , and Cu<sub>2</sub>MoO<sub>5</sub>. After annealing at 500 °C in H<sub>2</sub>, reflections corresponding to metallic Cu and molybdenum dioxide  $(MoO<sub>2</sub>)$  are evident, indicating partial reduction of the  $Cu<sub>x</sub>$ - $Mo<sub>y</sub>O<sub>z</sub>$  powder. Above 800 °C, only metallic (Cu) and (Mo) diffraction peaks are present, indicating complete reduction of the oxide precursor.

The as-prepared powders are approximately 5 to 10 nm in size and tend to agglomerate into larger powder clusters of approximately 50 nm in size, as shown in Figure  $2(a)$ for as-prepared Ag-Mo-O. After annealing at 500  $^{\circ}$ C for 2 hours in  $H<sub>2</sub>$ , the Cu particle size increases to approximately 500 nm, and the particle size of the Mo-rich phase increases to approximately 150 nm, as shown in Figure 2(b). Sintering Cu-Mo at 1050 °C in  $H_2$  for 1 hour yields a uniform distribution of Cu and Mo grains and an average grain size of approximately 0.5  $\mu$ m, as shown in Figure 2(c). Phases in the heat-treated alloys were identified by spot EDS analysis.

Table I shows the average coefficient of thermal expansion (CTE) in the temperature range of 25  $\degree$ C to 100  $\degree$ C, electrical conductivity, estimated thermal conductivity, and hardness Fig. 1—XRD patterns of sample A (52.5 wt pct Cu-47.5 wt pct Mo): (a)<br>as-prepared copper molybdate precursor and after annealing in H<sub>2</sub> at (b)<br>500 °C and (c) 1050 °C.<br>500 °C and (c) 1050 °C. and close to Cu-Mo and Ag-Mo values predicted by a ruleof-mixtures, or isostress, model. Electrical conductivity decreases with increasing molybdenum content. Hardness values of sintered Cu-Mo and Ag-Mo are high due to the

Sample identifications and compositions as determined Ag-Mo alloys prepared by this method are comparable to

**Table I. Sample Identification, Composition, and Properties of Sintered Cu-Mo and Ag-Mo**

Sample	Composition, Wt Pct	Average CTE, $^{\circ}$ C <sup>-1</sup>	Electrical Conductivity, S/cm	<b>Estimated Thermal</b> Conductivity, $W/m \cdot K$	Hardness, $HV_{5k\sigma}$
А	52.5Cu - 47.5Mo	$11.9 \times 10^{-6}$	$3.2 \times 10^5$	240	200
B	44.6Cu - 55.4Mo	$9.98 \times 10^{-6}$	$2.9 \times 10^5$	210	252
$\mathcal{C}$	36.1Cu - 63.9Mo	$8.65 \times 10^{-6}$	$2.9 \times 10^{5}$	210	257
D	$44.0Ag - 56.0Mo$	$10.2 \times 10^{-6}$	$2.7 \times 10^5$	200	239
Е	$38.1Ag - 61.9Mo$	$9.48 \times 10^{-6}$	$2.3 \times 10^{5}$	170	251



Fig. 2—SEM images of Ag-Mo and Cu-Mo: (*a*) sample D (44 wt pct Ag-56 wt pct Mo) as-prepared powder agglomerates, (*b*) sample A (52.5 wt pct Cu-47.5 wt pct Mo) after annealing in H<sub>2</sub> at 500 °C for 2 h, and (*c*) sample A (52.5 wt pct Cu-47.5 wt pct Mo) after sintering in H<sub>2</sub> at 1050 °C (backscattered electron image). In Fig. 2(b), the large, darker particles are Cu and small, and the lighter particles are MoO<sub>2</sub>. In Fig. 2(c), light grains are (Mo), dark gray grains are (Cu), and black spots are pores.

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